

## Search Notes



Application No.

10/630,716

Applicant(s)

FUKUYAMA ET AL.

Examiner

Stephen W. Smoot

Art Unit

2813

## SEARCHED

Class	Subclass	Date	Examiner
438	623	8/20/2004	SWS
438	624	6/20/2004	SWS
438	637	6/20/2004	SWS
438	638	6/20/2004	SWS
438	675	8/20/2004	SWS
438	763	8/20/2004	SWS
438	780	8/20/2004	SWS
257	635	8/20/2004	SWS
257	637	8/20/2004	SWS
257	642	8/20/2004	SWS
257	774	8/20/2004	SWS
257	775	8/20/2004	SWS
257	E23.145	8/20/2004	SWS
Updated	Above	2/3/2005	SWS

Updated Above Search 5-16-05 S.W.S.

## INTERFERENCE SEARCHED

Class	Subclass	Date	Examiner
Same as Above		5/16/2005	SWS

SEARCH NOTES  
(INCLUDING SEARCH STRATEGY)

	DATE	EXMR
Key Words: Low Dielectric Constant - Low k, Low Permittivity; Contact Hole, Opening Via; Interconnect - Trace, Line, Wiring;	8/20/2004	S.W.S.
Interlayer, ILD, IMD - Organic, Porous Silica; Borderless Contact; Transistor - Source, Gate, Drain.	8/20/2004	S.W.S.
Updated Above Search	2/3/2005	S.W.S.
Updated Above Search	5/16/2005	S.W.S.
Search Tools - EAST (attached): USPAT; US PG PUBS; Derwent; EPO; JPO; IBM TDB	8/20/2004; 2-3-05; 8	SWS
	5-16-05	S.W.S.